

U.S. UTILITY Patent Application

O.I.P.E.

PATENT DATE

SCANNED

Q.A.

Project 2/11/02 Res. A. 11/02

APPLICATION NO. 09/966080	CONT/PRIOR F	CLASS 438 430	SUBCLASS 3-1 329	ART UNIT 1756 2812 1755	EXAMINER Danda Rugg
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APPLICANTS

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TIME

Method for fabricating a resist pattern, a method for patterning a thin film and a method for manufacturing a micro device

PTO-204
12/89

ISSUING CLASSIFICATION

[illegible]

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<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			Amount Allowed	
	Sheets Draw.	Figs. Draw.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent is for years _____ (date)				NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall be for years _____ No. _____					
				Amount Due	Date Paid

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